

Characterization of Photo resist: SPR955-0.9

Exposed by GCA Autostep(new)

Conditions:

Focus offset: -7 -> 11 (inc:3)
Exposure time: 0.2s -> 0.8s (inc:0.1s)
Coating photo resist: 3000rpm (recipe 5)
Soft bake: 90s@95C
Post bake: 90s@110C
Develop: 60s MF701

Exposure time →

0.2s 0.3s 0.4s 0.5s 0.6s 0.7s 0.8s

Focus offset ↓

-7	71	72	73	74	75	76	77
-4	61	62	63	64	65	66	67
-1	51	52	53	54	55	56	57
2	41	42	43	44	45	46	47
5	31	32	33	34	35	36	37
8	21	22	23	24	25	26	27
11	11	12	13	14	15	16	17

Autostep200(new stepper) 0.7 lines

SPR 955-0.9

0.2s

0.3s

0.4s

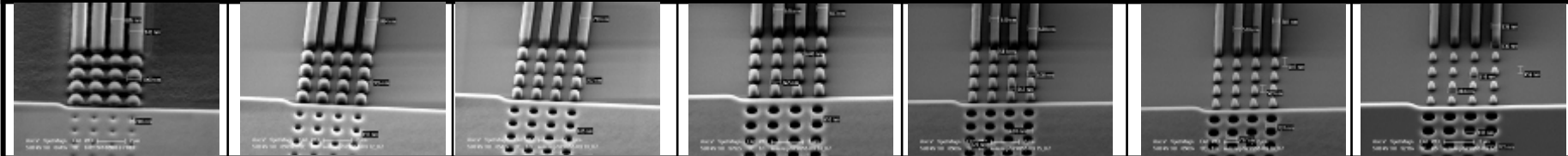
0.5s

0.6s

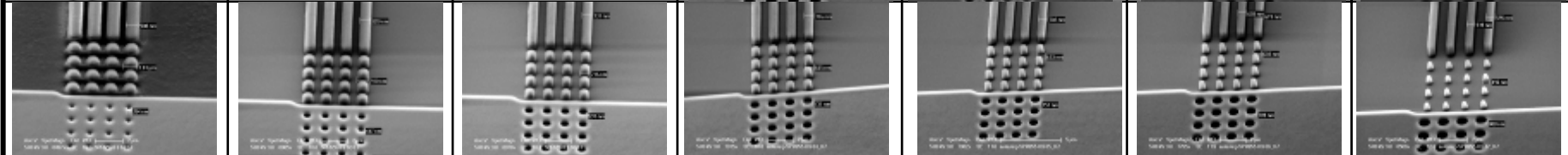
0.7s

0.8s

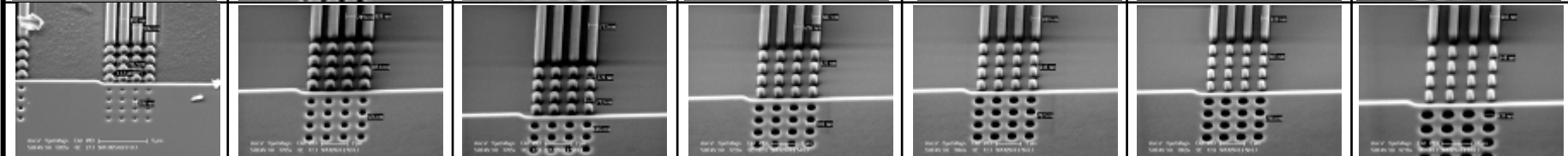
-7



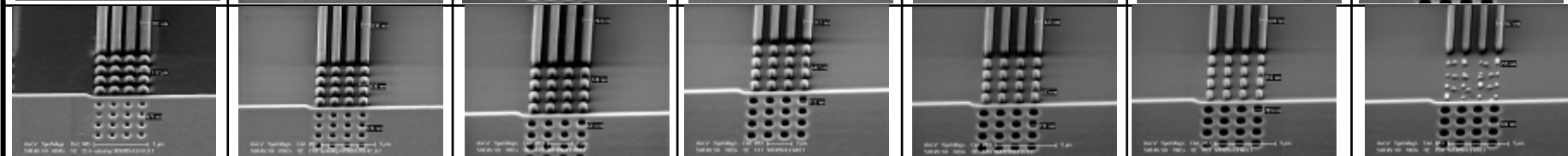
-4



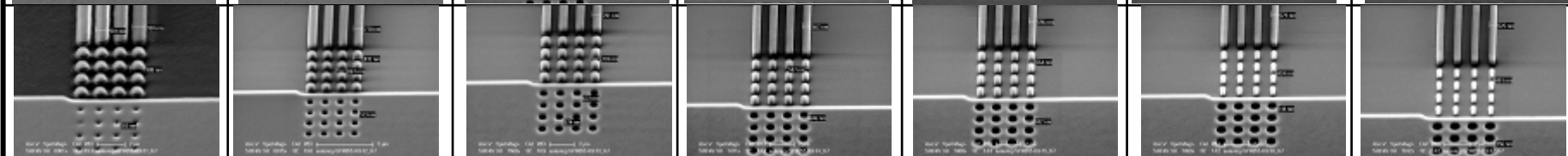
-1



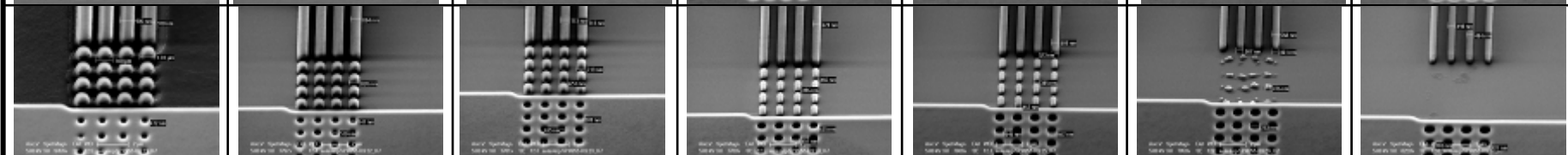
2



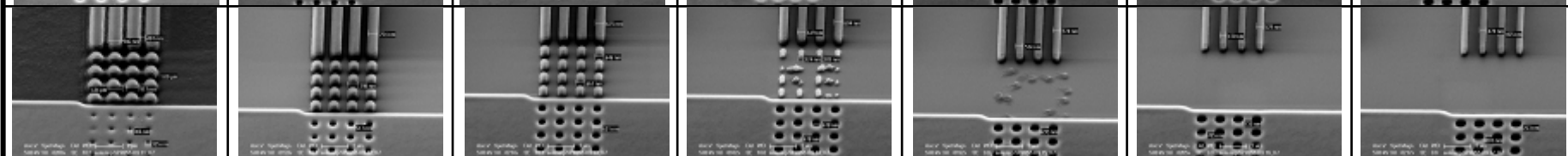
4



7



11



Autostep200(new stepper) 0.5 lines

SPR 955-0.9

0.15s

0.2s

0.25s

0.35s

0.4s

0.45s

0.5s

-7

-4

-1

2

4

7

11

